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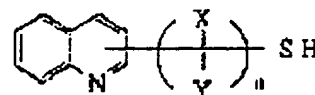
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(54) PREPARATION OF ION EXCHANGE RESIN AND BISPHENOL USING ION EXCHANGE RESIN

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a preparation process for modified strong acidic sulfonic acid type ion exchange resin of high conversion rate of acetone and high selection ratio of 4,4'-bisphenol A and of good stability and useful as a catalyst for preparing bisphenol A by the condensation reaction of phenol with acetone and also for bisphenol using the above ion exchange resin.

SOLUTION: 1. A modified strong acidic sulfonic acid type ion exchange resin is prepared by ion bonding quinolines having a mercapto group represented by the formula with strong acidic sulfonic acid type ion exchange resin. In the formula, X and Y represent respectively and independently hydrogen atom, 1 or 2C alkyl, 5 to 10C cycloalkyl or aryl, and (n) represents 2 to 4 integer. The bonding position of a substituent containing a mercapto group is anyone of ranks of 2, 3, 4, 6 or 8 of quinoline. 2. Bisphenol is prepared by reacting phenol with ketones under the presence of the modified strong acidic sulfonic acid type ion exchange resin referred in the above item 1.



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